

Paths of analysis*

Y3A

Synthia

October 10, 2022

1 Analysis parameters

Analysis type: Automatic Retrosynthesis

Rules: none selected

Filters: Exclude Diastereoselective reactions, Tunnels, FGI, FGI with protections

Max. paths returned: 50

Max. iterations: 2000

Commercial:

1. Max. molecular weight - 1000 g/mol
2. Max. price - 1500 \$/g

Published:

1. Max. molecular weight - 1000 g/mol
2. Popularity - 5

My Stockroom:

1. Max. molecular weight - 1000 g/mol

Reaction scoring formula: $\text{TUNNEL_COEF} * \text{FGI_COEF} * \text{STEP} * 20 + 100000 * (\text{CONFLICT} + \text{NON_SELECTIVITY} + \text{FILTERS} + \text{PROTECT})$

Chemical scoring formula: $\text{SMALLER}^3, \text{SMALLER}^{1.5}$

Min. search width: 400

Max. reactions per product: 60

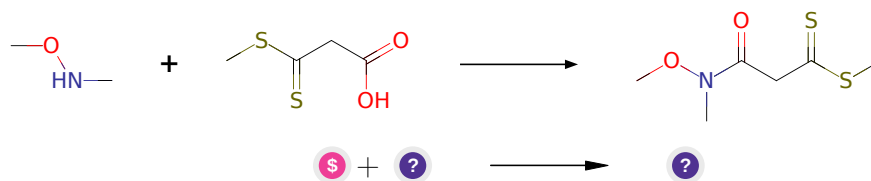
*The results stated herein were generated using the proprietary platform owned and maintained by Grzybowski Scientific Inventions, Inc., a subsidiary of Merck KGaA, Darmstadt Germany. The results are provided on an as is basis, and shall be used solely in connection with the rights afforded in the license agreement and for no other purpose.

JSON Parameters: `{}`

Reference: [10.1021/jacs.8b12242](#) SI p. S25 and [10.1021/ol5025025](#) SI p. S27

Retrosynthesis ID: 10366

2.1.2 Synthesis of O-substituted N-substituted hydroxamic acids



Substrates:

1. n-methoxymethylamine - *available at Sigma-Aldrich*
2. CSC(=S)CC(=O)O

Products:

1. CON(C)C(=O)CC(=S)SC

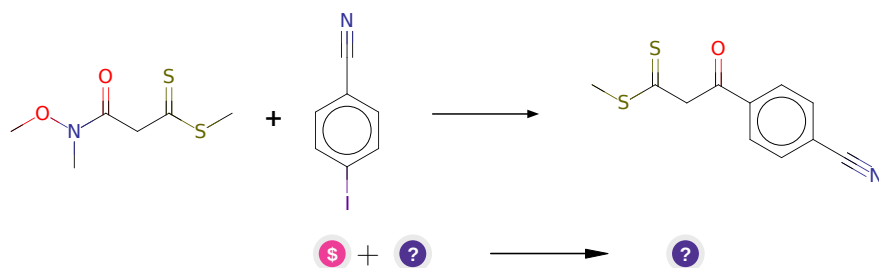
Typical conditions: DCC.DMAP or CDI.TEA.DCM

Protections: none

Reference: Patent: WO2007/67333A2, 2007 & *10.1016/j.bmcl.2008.09.100*

Retrosynthesis ID: 1152

2.1.3 Synthesis of ketones from Weinreb amides



Substrates:

1. 4-Iodobenzonitrile - *available at Sigma-Aldrich*
2. CON(C)C(=O)CC(=S)SC

Products:

1. CSC(=S)CC(=O)c1ccc(C#N)cc1

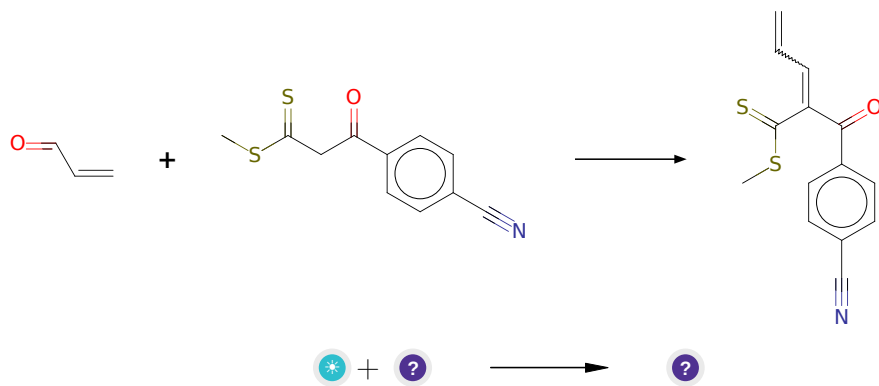
Typical conditions: 1.RmgBr.THF 2.TFA.DCM

Protections: none

Reference: [10.1021/jm051185t](#) and [10.1021/ol101021v](#) (supporting info)

Retrosynthesis ID: 5060

2.1.4 Aldol Condensation



Substrates:

1. Acrolein
2. CSC(=S)CC(=O)c1ccc(C#N)cc1

Products:

1. C=CC=C(C(=O)c1ccc(C#N)cc1)C(=S)SC

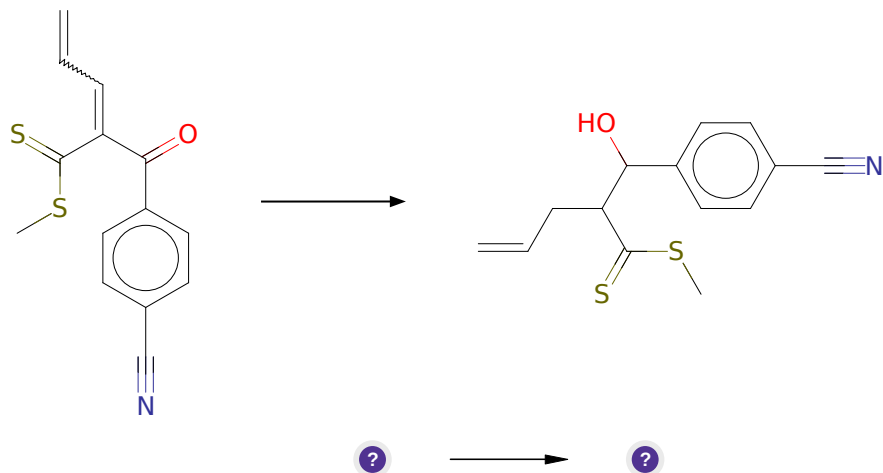
Typical conditions: NaOEt.base

Protections: none

Reference: [10.1080/00397911.2016.1206938](#)

Retrosynthesis ID: 10049

2.1.5 Reduction of enones to saturated alcohols



Substrates:

1. C=CC=C(C(=O)c1ccc(C#N)cc1)C(=S)SC

Products:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

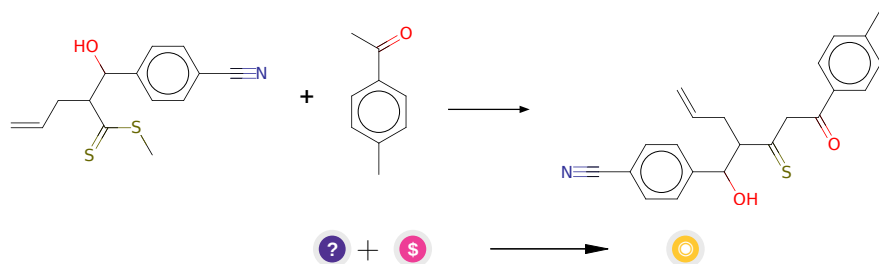
Typical conditions: NaBH₄.transition.metal.salt.(eg.Pd(OAc)₂.or.CeCl₃)

Protections: none

Reference: [10.1080/00397910902788117](#) AND [10.1021/jo00235a009](#)
AND [10.1016/0040-4020\(95\)00125-R](#) AND [10.1021/ja01327a041](#) AND
[10.1021/jo00302a056](#) AND [10.1002/adsc.200900628](#)

Retrosynthesis ID: 15304

2.1.6 Condensation of ketones with dithioesters



Substrates:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

2. Methyl p-tolyl ketone - *available at Sigma-Aldrich*

Products:

1. C=CCC(C(=S)CC(=O)c1ccc(C)cc1)C(O)c1ccc(C#N)cc1

Typical conditions: NaH.DMF

Protections:

Functional group SMARTS	Classification	Protecting groups
[#6][CH]([#6])[OH]	alcohols	Methoxymethyl Ether (MOM)
		2-Methoxyethoxymethyl Ether (MEM)
		Tetrahydropyranyl Ether (THP)
		Benzyl Ether (PMB)
		t-Butyldimethylsilyl Ether (TB-DMS)
		Methyl Ether

Reference: [10.1021/jo400599e](#) and [10.1002/ejoc.201301667](#)

Retrosynthesis ID: 9996413

2.2 Path 2

Score: 1000151.35

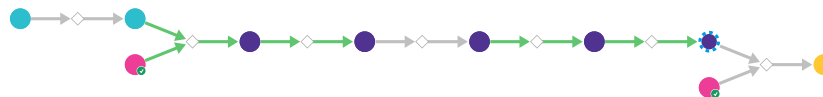
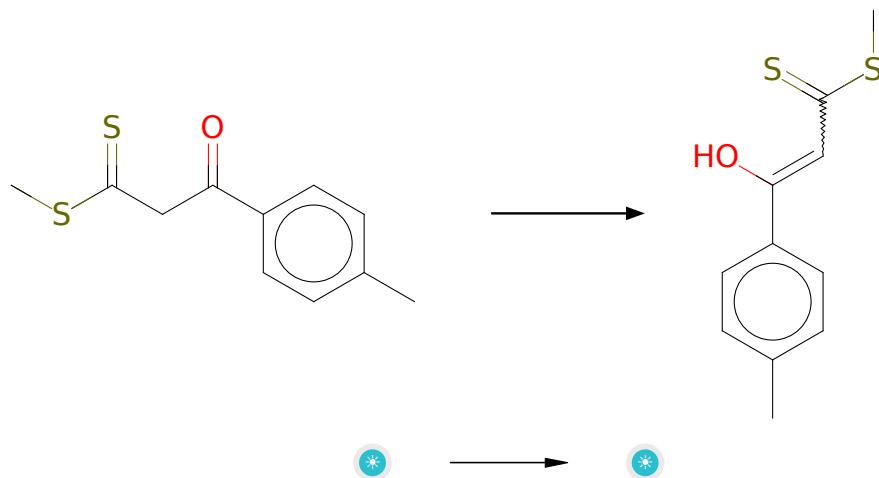


Figure 2: Outline of path 2

2.2.1 Keto-enol Tautomerism



Substrates:

1. 4-methyl-benzoyl-dithioacetic acid methyl ester (p-toluoyl-dithioacetic acid methyl ester)

Products:

1. 3-hydroxy-3-p-tolyl-dithioacrylic acid methyl ester

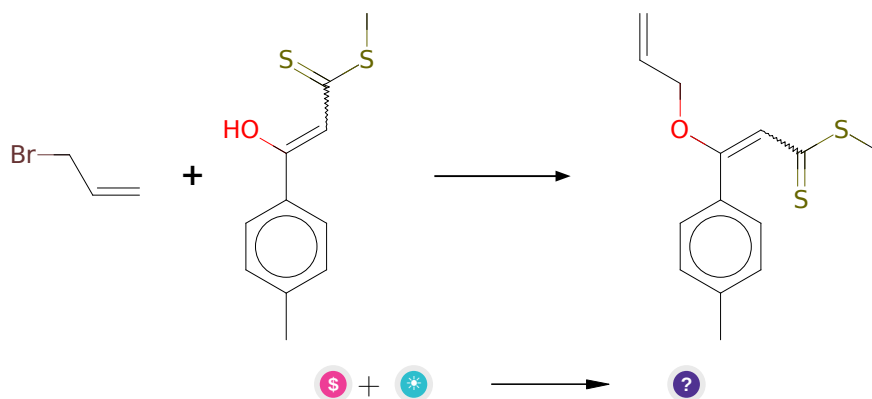
Typical conditions: solvent

Protections: none

Reference: [10.1021/ja01065a003](#) AND [10.1021/jo8012385](#)

Retrosynthesis ID: 7780

2.2.2 Enolate O-Alkylation



Substrates:

1. Allyl bromide - *available at Sigma-Aldrich*
2. 3-hydroxy-3-p-tolyl-dithioacrylic acid methyl ester

Products:

1. C=CCOC(=CC(=S)SC)c1ccc(C)cc1

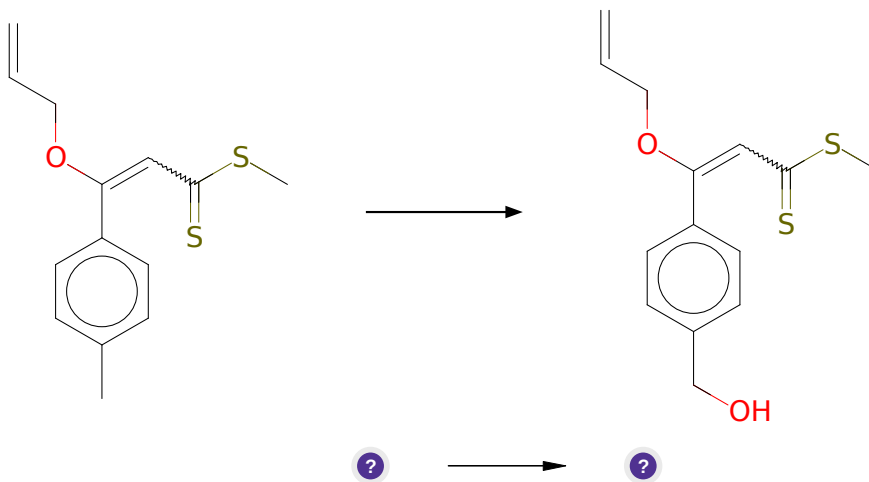
Typical conditions: Cs₂CO₃.DMF

Protections: none

Reference: [10.1016/j.bmcl.2012.05.070](#) and [10.1039/b612336h](#)

Retrosynthesis ID: 14841

2.2.3 Hydroxylation of benzylic position



Substrates:

1. C=CCOC(=CC(=S)SC)c1ccc(C)cc1

Products:

1. C=CCOC(=CC(=S)SC)c1ccc(CO)cc1

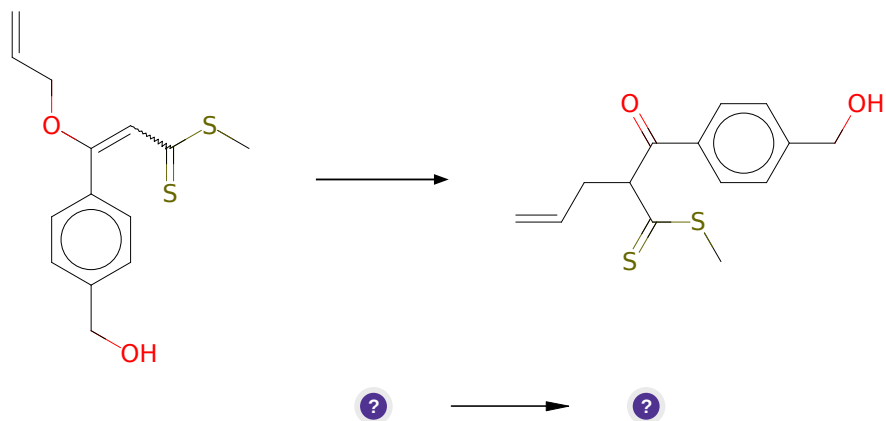
Typical conditions: 1.Ce(OTf)₄.MeCN.2.NaBH₄

Protections: none

Reference: [10.1039/B008843I](#) and WO2012137047 p.12

Retrosynthesis ID: 27139

2.2.4 Claisen Rearrangement



Substrates:

1. C=CCOC(=CC(=S)SC)c1ccc(CO)cc1

Products:

1. C=CCC(C(=O)c1ccc(CO)cc1)C(=S)SC

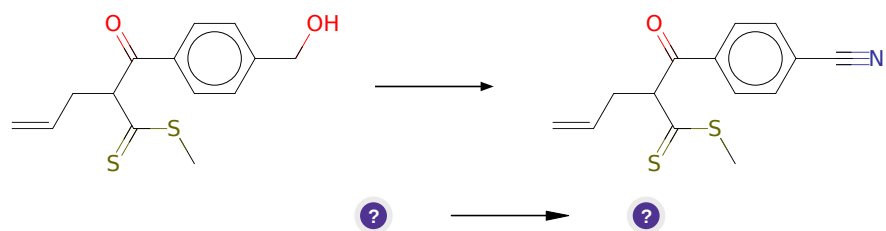
Typical conditions: heat

Protections: none

Reference: DOI: [10.1021/ja00206a017](https://doi.org/10.1021/ja00206a017) and [10.1016/S0022-1139\(98\)00313-3](https://doi.org/10.1016/S0022-1139(98)00313-3)

Retrosynthesis ID: 1226

2.2.5 Synthesis of nitriles from alcohols



Substrates:

1. C=CCC(C(=O)c1ccc(CO)cc1)C(=S)SC

Products:

1. C=CCC(C(=O)c1ccc(C#N)cc1)C(=S)SC

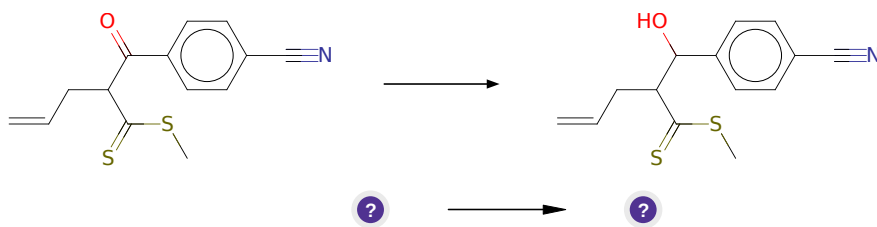
Typical conditions: 1) TEMPO.DCM.rt. 2) NH₃.I₂ or NH₃.tBuOCl

Protections: none

Reference: [10.1055/s-0033-1338489](#)

Retrosynthesis ID: 50205

2.2.6 Reduction of ketones with NaBH₄



Substrates:

1. C=CCC(C(=O)c1ccc(C#N)cc1)C(=S)SC

Products:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

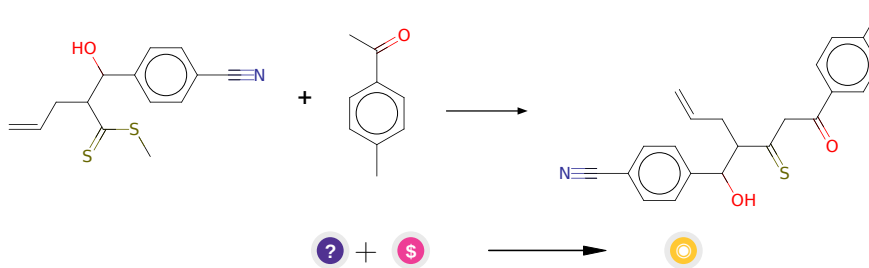
Typical conditions: NaBH₄.EtOH.0-20 C

Protections: none

Reference: [10.1016/j.ejmech.2020.112360](#) p. 3, 8 and [10.1016/j.ejmech.2010.10.012](#) p. 434, 436

Retrosynthesis ID: 50432

2.2.7 Condensation of ketones with dithioesters



Substrates:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1
2. Methyl p-tolyl ketone - [available at Sigma-Aldrich](#)

Products:

1. C=CCC(C(=S)CC(=O)c1ccc(C)cc1)C(O)c1ccc(C#N)cc1

Typical conditions: NaH.DMF

Protections:

Functional group SMARTS	Classification	Protecting groups
[#6][CH]([#6])[OH]	alcohols	Methoxymethyl Ether (MOM)
		2-Methoxyethoxymethyl Ether (MEM)
		Tetrahydropyranyl Ether (THP)
		Benzyl Ether (PMB)
		t-Butyldimethylsilyl Ether (TB-DMS)
		Methyl Ether

Reference: [10.1021/jo400599e](#) and [10.1002/ejoc.201301667](#)

Retrosynthesis ID: 9996413

2.3 Path 3

Score: 1000151.35

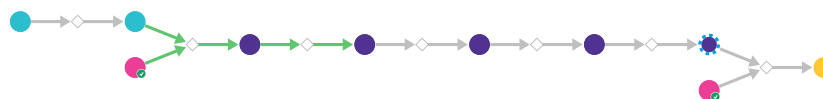
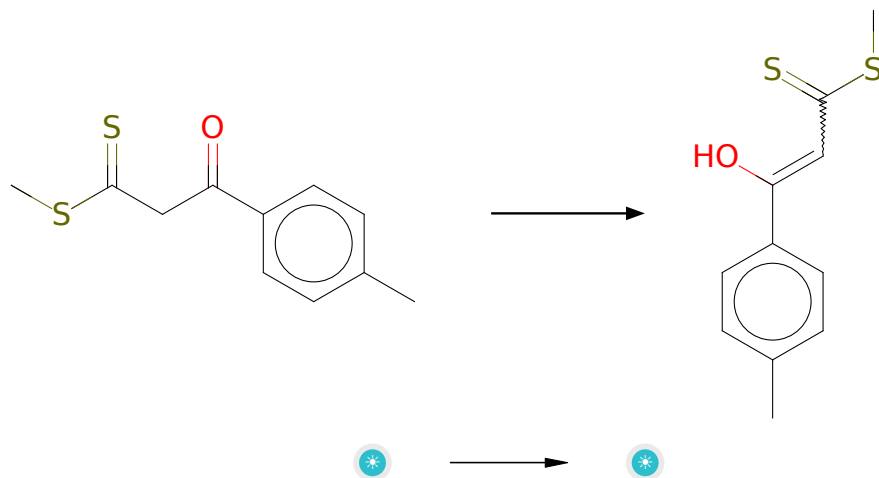


Figure 3: Outline of path 3

2.3.1 Keto-enol Tautomerism



Substrates:

1. 4-methyl-benzoyl-dithioacetic acid methyl ester (p-toluoyl-dithioacetic acid methyl ester)

Products:

1. 3-hydroxy-3-p-tolyl-dithioacrylic acid methyl ester

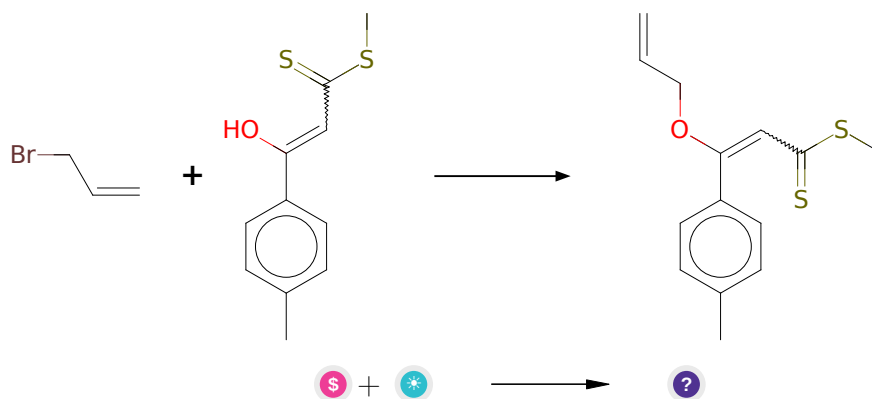
Typical conditions: solvent

Protections: none

Reference: [10.1021/ja01065a003](#) AND [10.1021/jo8012385](#)

Retrosynthesis ID: 7780

2.3.2 Enolate O-Alkylation



Substrates:

1. Allyl bromide - *available at Sigma-Aldrich*
2. 3-hydroxy-3-p-tolyl-dithioacrylic acid methyl ester

Products:

1. C=CCOC(=CC(=S)SC)c1ccc(C)cc1

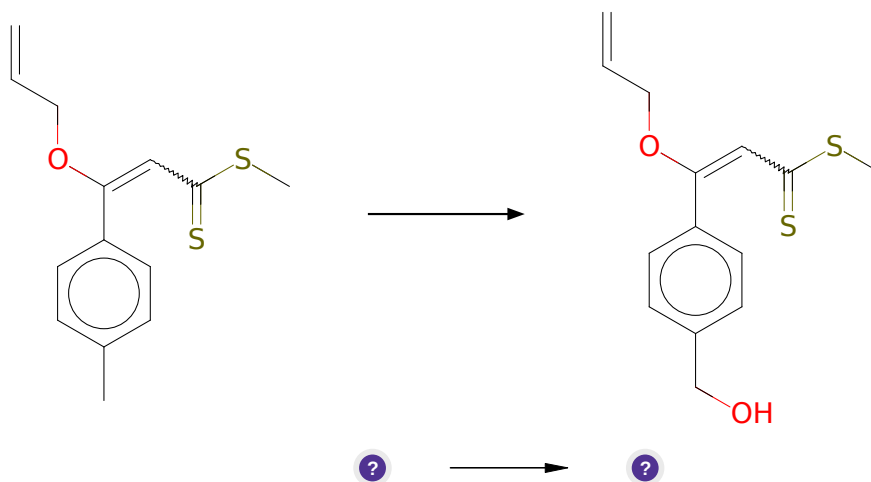
Typical conditions: Cs₂CO₃.DMF

Protections: none

Reference: [10.1016/j.bmcl.2012.05.070](#) and [10.1039/b612336h](#)

Retrosynthesis ID: 14841

2.3.3 Hydroxylation of benzylic position



Substrates:

1. C=CCOC(=CC(=S)SC)c1ccc(C)cc1

Products:

1. C=CCOC(=CC(=S)SC)c1ccc(CO)cc1

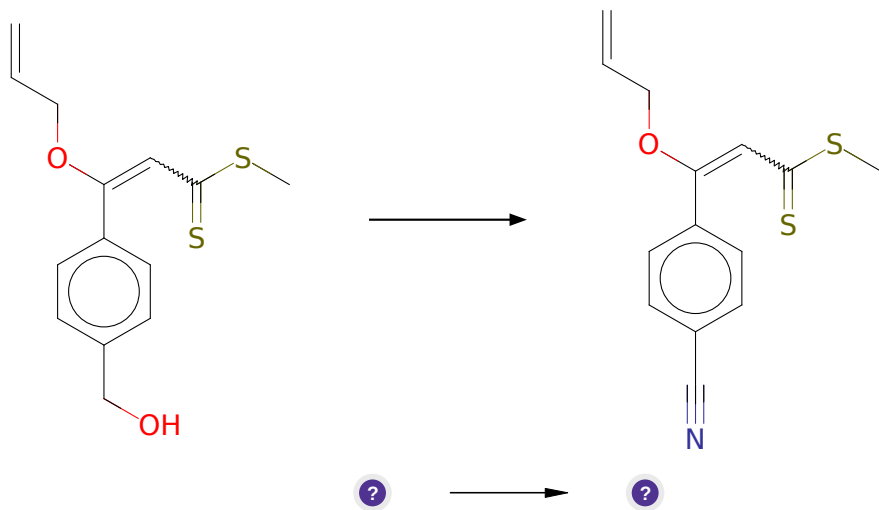
Typical conditions: 1.Ce(OTf)₄.MeCN.2.NaBH₄

Protections: none

Reference: [10.1039/B008843I](#) and WO2012137047 p.12

Retrosynthesis ID: 27139

2.3.4 Conversion of Alcohols into Nitriles



Substrates:

1. C=CCOC(=CC(=S)SC)c1ccc(CO)cc1

Products:

1. C=CCOC(=CC(=S)SC)c1ccc(C#N)cc1

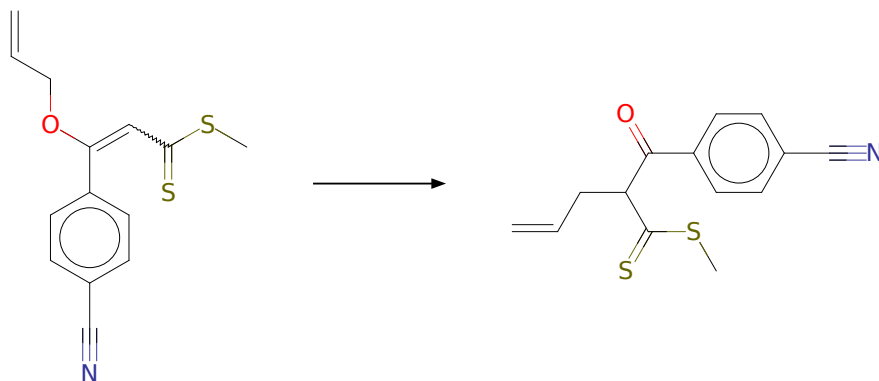
Typical conditions: I2.RT

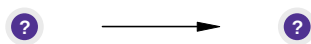
Protections: none

Reference: DOI: [10.1021/jo0625352](https://doi.org/10.1021/jo0625352)

Retrosynthesis ID: 10973

2.3.5 Claisen Rearrangement





Substrates:

1. C=CCOC(=CC(=S)SC)c1ccc(C#N)cc1

Products:

1. C=CCC(C(=O)c1ccc(C#N)cc1)C(=S)SC

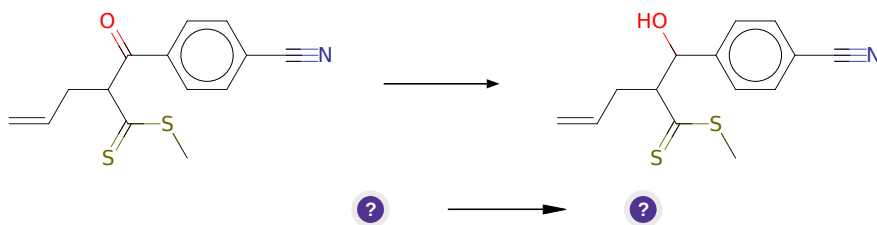
Typical conditions: heat

Protections: none

Reference: DOI: [10.1021/ja00206a017](https://doi.org/10.1021/ja00206a017) and [10.1016/S0022-1139\(98\)00313-3](https://doi.org/10.1016/S0022-1139(98)00313-3)

Retrosynthesis ID: 1226

2.3.6 Reduction of ketones with NaBH₄



Substrates:

1. C=CCC(C(=O)c1ccc(C#N)cc1)C(=S)SC

Products:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

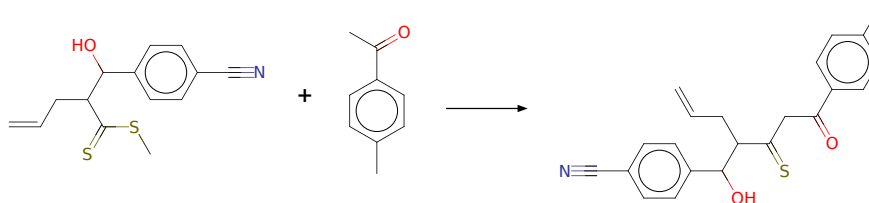
Typical conditions: NaBH₄.EtOH.0-20 C

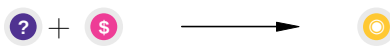
Protections: none

Reference: [10.1016/j.ejmech.2020.112360](https://doi.org/10.1016/j.ejmech.2020.112360) p. 3, 8 and [10.1016/j.ejmech.2010.10.012](https://doi.org/10.1016/j.ejmech.2010.10.012) p. 434, 436

Retrosynthesis ID: 50432

2.3.7 Condensation of ketones with dithioesters





Substrates:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1
2. Methyl p-tolyl ketone - *available at Sigma-Aldrich*

Products:

1. C=CCC(C(=S)CC(=O)c1ccc(C)cc1)C(O)c1ccc(C#N)cc1

Typical conditions: NaH.DMF

Protections:

Functional group SMARTS	Classification	Protecting groups
[#6][CH]([#6])[OH]	alcohols	Methoxymethyl Ether (MOM)
		2-Methoxyethoxymethyl Ether (MEM)
		Tetrahydropyranyl Ether (THP)
		Benzyl Ether (PMB)
		t-Butyldimethylsilyl Ether (TB-DMS)
		Methyl Ether

Reference: [10.1021/jo400599e](#) and [10.1002/ejoc.201301667](#)

Retrosynthesis ID: 9996413

2.4 Path 4

Score: 1000161.11

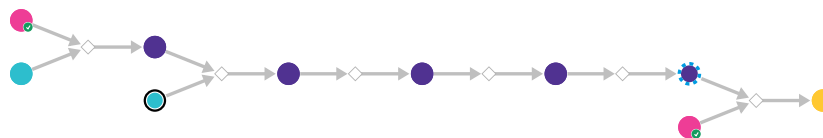
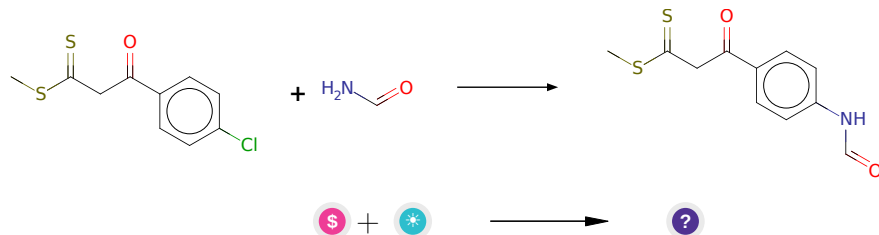


Figure 4: Outline of path 4

2.4.1 Arylation of amides with aryl chlorides



Substrates:

1. Amide C1 - *available at Sigma-Aldrich*
2. p-chlor-benzoyl-dithioessigsaeure-methylester

Products:

1. CSC(=S)CC(=O)c1ccc(NC=O)cc1

Typical conditions:
CuI.diamine.base.DMF.heat

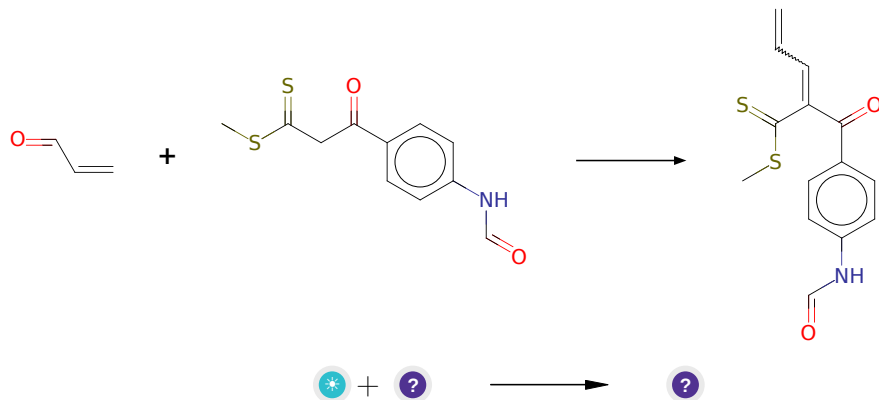
Base.[Pd].catalyst.dioxane.heat or

Protections: none

Reference: [10.1021/ja0717414](#) and [10.1016/j.tet.2009.04.096](#) and [10.1002/chem.201302453](#) and [10.1080/00397911.2016.1195844](#)

Retrosynthesis ID: 10012552

2.4.2 Aldol Condensation



Substrates:

1. Acrolein

2. CSC(=S)CC(=O)c1ccc(NC=O)cc1

Products:

1. C=CC=C(C(=O)c1ccc(NC=O)cc1)C(=S)SC

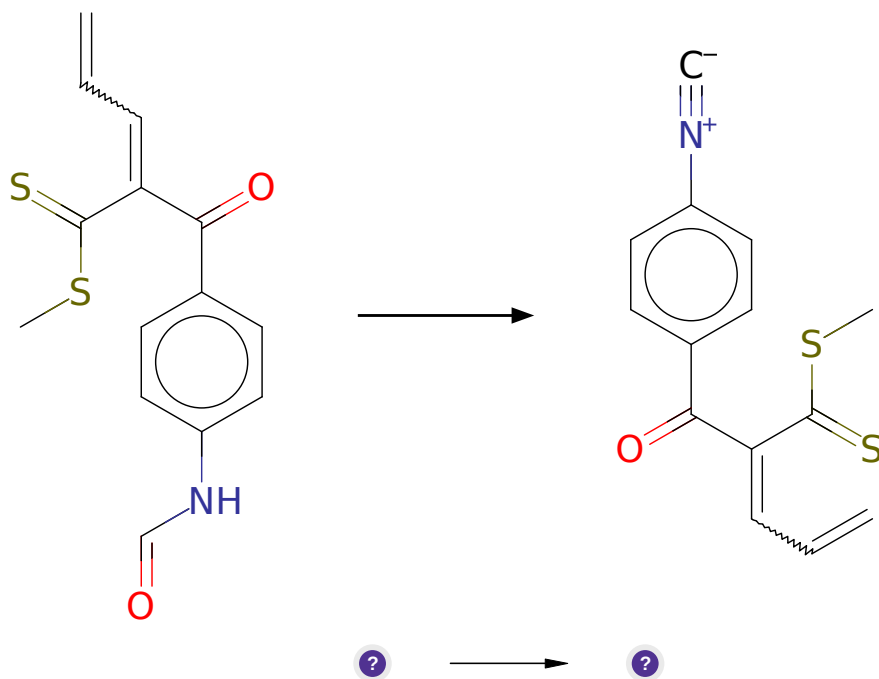
Typical conditions: NaOEt.base

Protections: none

Reference: [10.1080/00397911.2016.1206938](#)

Retrosynthesis ID: 10049

2.4.3 Synthesis of isocyanides from formamides



Substrates:

1. C=CC=C(C(=O)c1ccc(NC=O)cc1)C(=S)SC

Products:

1. [C-]#[N+]c1ccc(C(=O)C(=CC=C)C(=S)SC)cc1

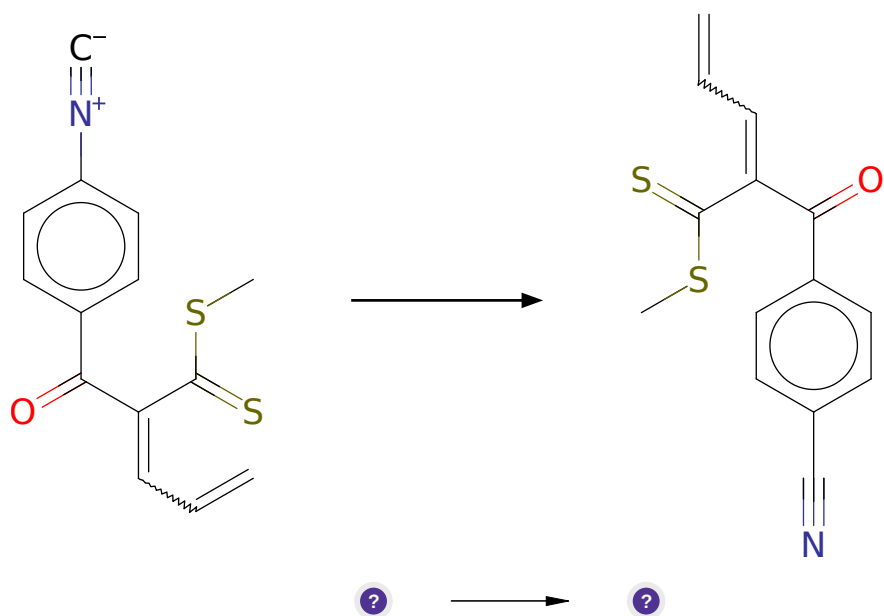
Typical conditions: TCT.DCM.TEA.MW.50-100C

Protections: none

Reference: DOI: [10.1021/jo047924f](https://doi.org/10.1021/jo047924f)

Retrosynthesis ID: 245867

2.4.4 Isonitrile-Nitrile Rearrangement



Substrates:

1. [C-]#[N+]c1ccc(C(=O)C(=CC=C)C(=S)SC)cc1

Products:

1. C=CC=C(C(=O)c1ccc(C#N)cc1)C(=S)SC

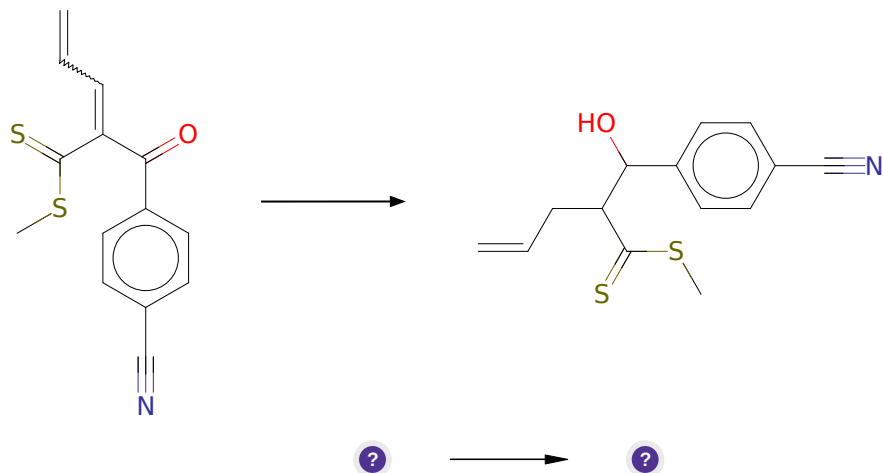
Typical conditions: (1-phenylethenyl)benzene.50C

Protections: none

Reference: DOI: [10.1021/jo00380a028](https://doi.org/10.1021/jo00380a028)

Retrosynthesis ID: 10398

2.4.5 Reduction of enones to saturated alcohols



Substrates:

1. C=CC=C(C(=O)c1ccc(C#N)cc1)C(=S)SC

Products:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

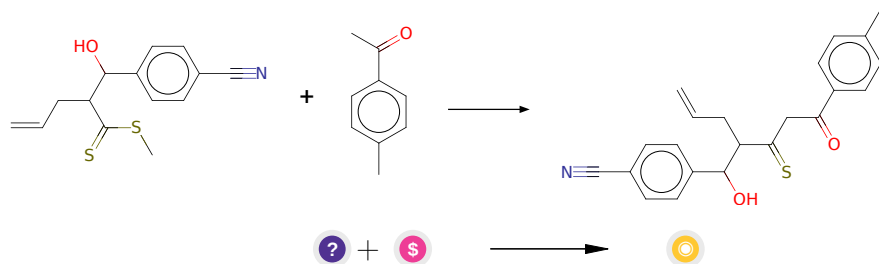
Typical conditions: NaBH₄.transition.metal.salt.(eg.Pd(OAc)₂.or.CeCl₃)

Protections: none

Reference: [10.1080/00397910902788117](#) AND [10.1021/jo00235a009](#)
AND [10.1016/0040-4020\(95\)00125-R](#) AND [10.1021/ja01327a041](#) AND
[10.1021/jo00302a056](#) AND [10.1002/adsc.200900628](#)

Retrosynthesis ID: 15304

2.4.6 Condensation of ketones with dithioesters



Substrates:

1. C=CCC(C(=S)SC)C(O)c1ccc(C#N)cc1

2. Methyl p-tolyl ketone - *available at Sigma-Aldrich*

Products:

1. C=CCC(C(=S)CC(=O)c1ccc(C)cc1)C(O)c1ccc(C#N)cc1

Typical conditions: NaH.DMF

Protections:

Functional group SMARTS	Classification	Protecting groups
[#6][CH]([#6])[OH]	alcohols	Methoxymethyl Ether (MOM)
		2-Methoxyethoxymethyl Ether (MEM)
		Tetrahydropyranyl Ether (THP)
		Benzyl Ether (PMB)
		t-Butyldimethylsilyl Ether (TB-DMS)
		Methyl Ether

Reference: *10.1021/jo400599e* and *10.1002/ejoc.201301667*

Retrosynthesis ID: 9996413